

ABSTRACT

A cleaning device includes: a substrate rotation mechanism that holds a substrate and rotates the substrate around a center axis of the substrate as a rotation axis; a first single-tube nozzle that discharges a first cleaning liquid toward a top surface of the substrate held by the substrate rotation mechanism; and a second single-tube nozzle that discharges a second cleaning liquid toward the top surface of the substrate held by the substrate rotation mechanism separately from the first single-tube nozzle. The first single-tube nozzle and the second single-tube nozzle are disposed such that the second single-tube nozzle discharges the second cleaning liquid in a forward direction of a rotation direction of the substrate at a position farther away from the center of the substrate than a landing position of the first cleaning liquid, and a part is generated in which a liquid flow on the top surface of the substrate after landing of the first cleaning liquid and a liquid flow on the top surface of the substrate after landing of the second cleaning liquid are combined.

Figure 2